



Software solutions for
optimizing micro & nano
fabrication processes



Announcement

BEAMeeting MNE 2020 will be ON-LINE!!!

Online BEAMeeting MNE 2020 Technical Workshop & Discussion September 14th & 15th, 2020

Time: Monday 09:00 until 12:00 Online - Training & Workshop
Monday 13:30 – 17: 00 and Tuesday 9:00 - 12:30 On-Line BEAMeeting
Tuesday 14:00 LASER lithography session with Heidelberg Instruments

Location: Web via TEAMS (invitation will be sent after registration)

BEAMeetings are a technical exchange platform for the direct write community focused on e-beam and laser lithography, data-preparation, PEC, process correction, and lithography simulation. With the cancellation of the MNE 2020 conference originally scheduled for Sep 14-18 due to the Covid-19 situation, our traditional BEAMeeting at EIPBN is moving to an on-line format. The global GenISys team will contribute with updates on new features and applications. As always, we like to setup the agenda with your input!

The agenda is still in planning, the presentations will generally cover the following areas:

- BEAMER and TRACER: Data preparation using new features and enhancements
- LAB: Lithography simulation for optical and e-beam lithography
- ProSEM: Update on our SEM metrology software
- Exposure optimization (fracturing, field positioning/ordering, exposure order within the field)
- 3D and binary laser lithography using BEAMER and LAB
- User presentations

We encourage user presentations, and welcome any connected with nanolithography. This meeting is also an alternative venue to present research that was scheduled for presentation at MNE. Please contact us if you would like to present your work. If you have any colleagues who may be interested in the workshop, we would greatly appreciate your forwarding this information on to them.

To register and for presentation please send an e-mail to marketing@genisys-gmbh.com. We will send the final agenda beginning of September and provide on-line access data for those registering for on-line attendance.

We are looking forward to presenting you with an interesting and valuable workshop.

Thank you,

The GenISys Team